

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Sun et al

Serial No.: 10/616.097

Confirmation No.: 1645

Filed: July 8, 2003

For: Multiple-Step
Electrodepositon Process
for Direct Copper Plating
on Barrier Materials

Group Art Unit 1753

Examiner: Edna Wong

MAIL STOP AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

RESPONSE TO OFFICE ACTION DATED OCTOBER 17, 2006

In response to the Office Action dated October 17, 2006, having a shortened statutory period for response set to expire on January 17, 2007, please enter this Response and reconsider the claims pending in the application for the reasons discussed below. Although the Applicant believes that no additional fees are due in connection with this Response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/APPM/008241/JPC, for any fees, including extension of time fees or excess claim fees, required to make this Response timely and acceptable to the Office.

Amendments to the Claims begin on page 2 of this paper. **Remarks** begin on page 8 of this paper.

Page 1